

a transferring mechanism for receiving the dried substrate from the drying chamber through the second transferring port and for transferring the received substrate to the film forming chamber under the reduced pressure; and

a path for transferring the substrate between the transferring mechanism under reduced pressure and a location outside the apparatus under atmospheric pressure.

12. (twice-amended) An apparatus, comprising:

a first substrate carrier for transferring a substrate in an atmospheric air;
a first substrate processing portion performing a vacuum type processing on the substrate;
a second substrate processing portion performing a solution type processing on the substrate;
a first delivering and receiving portion delivering and receiving the substrate to be processed with the solution type processing between the second substrate processing portion and the first substrate processing portion; and
a second delivering and receiving portion delivering and receiving the substrate not to be processed with the solution type processing between the first substrate carrier and the first substrate processing portion.

Please insert new claims 23 - 25 as set forth below:

23. (New) The apparatus as set forth in claim 1,
wherein the path is connected to the first transferring port.

24. (New) The substrate processing apparatus as set forth in claim 1,
wherein a plurality of drying chambers are stacked vertically.

25. (New) The substrate processing apparatus as set forth in claim 1, further comprising:
an exhaust pipe for exhausting air from the at least one drying chamber.